

Technological approaches for modified multilayer coatings formation based on nanostructured porous anodic Al₂O₃ and deposited dielectric films

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Abstract. Technological methods and conditions for additional inorganic dielectric films formation using the vacuum deposition on nanostructured porous alumina bases are investigated. Modified multilayer structures with closed porosity have been obtained. The improvement of thermophysical and electrophysical properties of finite dielectric coatings on aluminum substrates is demonstrated.

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